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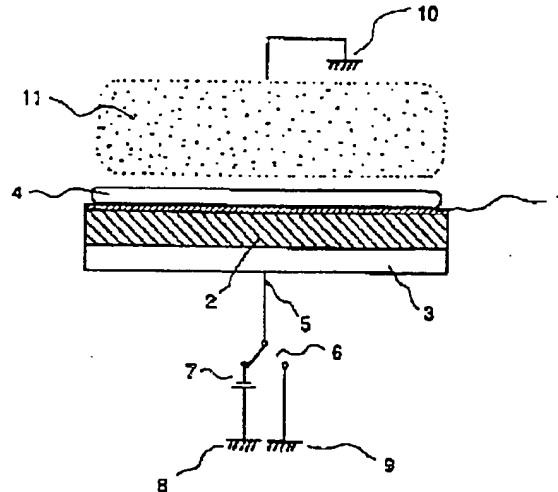
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TITLE : ELECTROSTATIC ATTRACTING
DEVICE



ABSTRACT : PROBLEM TO BE SOLVED: To suppress low the surface resistance of the dielectric film of an electrostatic attracting device and to make it possible to shorten a static discharging time, by a method wherein the dielectric film is formed into a structure, and a plurality of dielectric films of different resistivities are laminated.

SOLUTION: An electrostatic attracting device is constituted into a structure, wherein a first dielectric film 2 is adhered on an aluminium block 3 and a second dielectric film 1 is adhered on the film 2. The thickness of the film 2 is formed in about 250 μ m, the resistivity of the film 2 is set at about at 10¹¹ Ω cm, the thickness of the film 1 is formed in about 50 μ m, and the resistivity of the film 1 is set at about 10¹⁰ Ω cm. One end on one side of the ends of the block 3 is connected with an external DC power supply 7 via a conductor wire 5 and a ground line 8. By adhering the film 1 on the upper part of the film 2, the time constant of a charge stored in the dielectric film, which consists of the films 1 and 2, of the attracting device is decreased, and a static discharging time is shortened in the case where the surface resistance of the dielectric film is low. As a result, the surface resistance of the dielectric film is suppressed low and the static discharging time can be shortened.

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